

Serial No. 10/016,562

OFFICIAL

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant: Chang-Lin Hsieh.

Serial No.: 10/016,562

Filed: 12/12/2001

Title: Process for Selectively Etching Dielectric Layers

Art Unit: 1765

Examiner: Deo, Duy Vu Nguyen

Docket No.: 004544/ALRT/ETCH/DICP

VIA FACSIMILE 703-872-9311

Mail Stop Box AF

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

**RESPONSE TO OFFICE ACTION**

Sir:

This is responsive to the final Office Action mailed March 4, 2004 in the above matter.

251 North Avenue West, 2<sup>nd</sup> Floor  
Westfield, NJ 07090

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Oak Hill, Virginia 20171

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**Fax**

**To:** Commissioner for Patents

**From:** David Bonham  
(703) 433-0510

**Fax:** 703-872-9311

**Total pages:** 17

**Phone:**

**Date:** 6/4/2004

**Re:** In connection with the prosecution in Serial. No.  
10/016,562, please find enclosed a response to  
the Office Action mailed March 4, 2004.

**CC:**

Sincerely,

David Bonham

☐ Urgent    ☐ For Review    ☐ Please Comment    ☐ Please Reply    ☐ Please Recycle

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